IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

ர**ில்**ளீication Serial No. Filing Date October 283

Assignee Micron Technology, Inc Group Art Unit

Title: Capacitors and Methods of Forming Capacitors

To:

Assistant Commissioner for Patents

Washington, D.C. 20231

From:

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AMENDMENTS

In the Specification

Please replace the paragraph beginning at line 3 of page 8 with the following clean replacement paragraph in accordance with 37 C.F.R. § 1.121(b)(1)(ii):

--Accordingly in the above described preferred embodiment, first layer 18 of the capacitor dielectric layer material is essentially provided with a selected finished crystalline structure prior to formation of second layer 20 thereon. Such is achieved by the crystallization or recrystallization anneal immediately prior to formation of layer 20. Also in the preferred embodiment, the final composition of second layer 20 of the first material is also desirably formed to be crystalline, although alternately such could remain amorphous if so initially deposited. In the preferred embodiment